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(54) Title: EXTRUSION REDUCTION IN IMPRINT LITHOGRAPHY

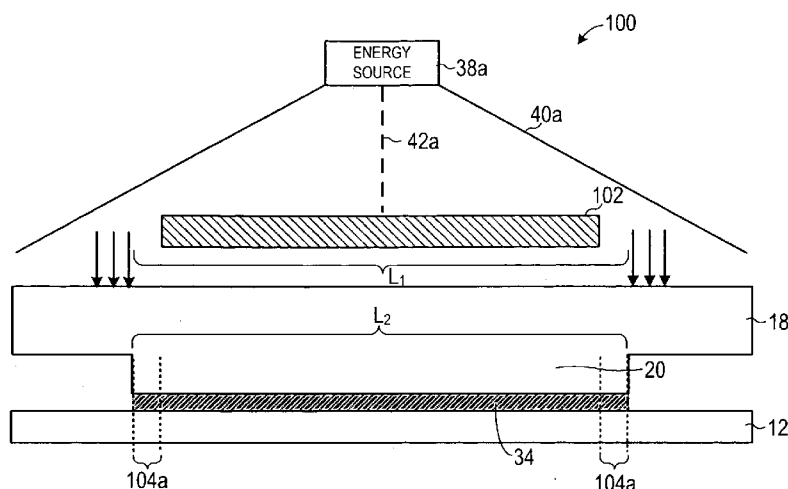


FIG. 5A

(57) Abstract: Devices positioned between an energy source and an imprint lithography template may block exposure of energy to portions of polymerizable material dispensed on a substrate. Portions of the polymerizable material that are blocked from the energy may remain fluid, while the remaining polymerizable material is solidified.